

*“Multiscale modeling of plasma–surface interaction—General picture and a case study of Si and SiO<sub>2</sub>etching by fluorocarbon-based plasmas”.* Vanraes P, Parayil Venugopalan S, Bogaerts A, Applied Physics Reviews **8**, 041305 (2021). <http://doi.org/10.1063/5.0058904>